

Process type factors	Gas /											
	CF <sub>4</sub>	C <sub>2</sub> F <sub>6</sub>	CHF <sub>3</sub>	CH <sub>2</sub> F <sub>2</sub>	C <sub>3</sub> F <sub>8</sub>	c-C <sub>4</sub> F <sub>8</sub>	NF <sub>3</sub> remote	NF <sub>3</sub>	SF <sub>6</sub>	C <sub>4</sub> F <sub>8</sub> <sup>a</sup>	C <sub>5</sub> F <sub>8</sub> <sup>a</sup>	C <sub>4</sub> F <sub>8</sub> O <sup>a</sup>
Etch 1-U <sub>1</sub>	0.7	0.4 <sup>1</sup>	0.4 <sup>1</sup>	0.06 <sup>1</sup>	N/A	0.2 <sup>1</sup>	N/A	0.2	0.2	0.1	0.2	N/A
Etch PCF <sub>4</sub>	N/A	0.4 <sup>1</sup>	0.07 <sup>1</sup>	0.08 <sup>1</sup>	N/A	0.2	N/A	N/A	N/A	0.3 <sup>1</sup>	0.2	N/A
Etch PC <sub>2</sub> F <sub>6</sub>	N/A	N/A	N/A	N/A	N/A	0.2	N/A	N/A	N/A	0.2 <sup>1</sup>	0.2	N/A
CVD 1-U <sub>1</sub>	0.9	0.6	N/A	N/A	0.4	0.1	0.02	0.2	N/A	N/A	0.1	0.1
CVD PCF <sub>4</sub>	N/A	0.1	N/A	N/A	0.1	0.1	0.02 <sup>2</sup>	0.1 <sup>2</sup>	N/A	N/A	0.1	0.1
CVD PC <sub>3</sub> F <sub>8</sub>	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	0.4

<sup>1</sup> Estimate includes multi-gas etch processes.

<sup>2</sup> Estimate reflects presence of low-k, carbide and multi-gas etch processes that may contain a fluorinated GHG greenhouse gas additive.